

IFW



Rev. 04/03

Docket No. ELM-1 Cont. 14

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Glenn J. Leedy  
Application No.: 10/766,557 Confirmation No.: 3092  
Filed : January 27, 2004  
For : METHODS FOR MASKLESS LITHOGRAPHY (AS AMENDED)  
Group Art Unit : 2812  
Examiner : Not yet assigned

New York, New York  
July 19, 2004

Hon. Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

TRANSMITTAL LETTER FOR  
INFORMATION DISCLOSURE STATEMENT

Sir:

Transmitted herewith is an Information Disclosure Statement in the above-identified application. This Statement is submitted:

- ☐ [ ] within three months of the application filing date;
- ☒ [X] more than three months from the application filing date but before the mailing date of the first Office Action on the merits.

In accordance with 37 C.F.R. § 1.97, submission of this Statement requires no fee. However, if for any reason a fee is due, the Director is hereby authorized to charge payment of any fees required in connection with this

Information Disclosure Statement to Deposit Account

No. 06-1075. A duplicate copy of this letter is transmitted herewith.

Respectfully submitted,

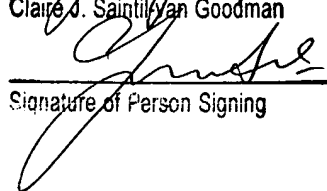


Philip R. Poh  
Registration No. 51,176  
Agent for Applicants  
FISH & NEAVE  
Customer No. 1473  
1251 Avenue of the Americas  
New York, New York 10020-1105  
Tel.: (212) 596-9000

I hereby certify that this  
Correspondence is being  
deposited with the U.S.  
Postal Service as First  
Class Mail in an envelope  
Addressed to:  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450 on

July 19, 2004

Claire J. Saintilryan Goodman



Signature of Person Signing



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Glenn J. Leedy  
Application No. : 10/766,557 Confirmation No.: 3092  
Filed : January 27, 2004  
For : METHODS FOR MASKLESS LITHOGRAPHY  
(AS AMENDED)  
Group Art Unit : 2812  
Examiner : Not yet assigned  
Hon. Commissioner for Patents  
P.O. Box 1450  
Alexandrian, Virginia 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.56 and 1.97,  
applicant wishes to call the attention of the Examiner to  
the following documents:

U.S. Patents

Fujii et al.	Re. 34,893	04/04/95
Foster	2,915,722	12/01/59
Farrand	3,202,948	08/24/65
Lesk	3,559,282	02/02/71
Burkhardt	3,560,364	02/02/71
Emmasingel	3,602,982	09/07/71
Medicus	3,615,901	10/26/71
Napoli et al.	3,716,429	02/13/73
Krishna et al.	3,777,227	12/14/73
Kuipers	3,868,565	02/25/75
Yerman	3,922,705	11/25/75
Wanlass	3,997,381	12/14/76
Stein	4,070,230	01/24/78
Greenwood et al.	4,131,985	01/02/79
Hauser, Jr., et al.	4,142,004	02/27/79

Hoeberechts	4,251,909	02/24/81
Kubacki	4,262,631	04/21/81
Shioya et al.	4,394,401	07/19/83
Trenkler et al.	4,401,986	08/30/83
Thomas et al.	4,416,054	11/22/83
Takagi et al.	4,539,068	09/03/85
Reid et al.	4,585,991	04/29/86
Yasumoto et al.	4,612,083	09/16/86
Belanger et al.	4,617,160	10/14/86
Shimizu et al.	4,618,397	10/21/86
Schmitz	4,618,763	10/21/86
Christensen	4,663,559	05/05/87
Burns et al.	4,684,436	08/04/87
Hatada	4,693,770	09/15/87
Maeda et al.	4,702,336	10/27/87
Seibert et al.	4,702,936	10/27/87
Go	4,706,166	11/10/87
Stevenson	4,721,938	01/26/88
Reid	4,761,681	08/02/88
Holmen et al.	4,784,721	11/15/88
Freeman	4,810,673	03/07/89
Mattox et al.	4,825,277	04/25/89
Tam et al.	4,857,481	08/15/89
Leedy	4,924,589	05/15/90
Borel et al.	4,940,916	07/10/90
Borel et al.	ReB14,940916	11/26/96
Vranish et al.	4,950,987	08/21/90
Lee et al.	4,952,446	08/18/90
Rokos	4,954,865	09/04/90
Shinomiya	4,957,882	09/18/90
Young et al.	4,965,415	10/23/90
Mauger	4,966,663	10/30/90
Leedy	4,994,735	02/19/91
Keogh et al.	5,008,619	04/16/91
Allen et al.	5,010,024	04/23/91
Leedy	5,020,219	06/04/91
Leedy	5,034,685	07/23/91
Greenwald et al.	5,070,026	12/03/91
Findler et al.	5,071,510	12/10/91
Machado et al.	5,098,865	03/24/92
Leedy	5,103,557	04/14/92
Mauger	5,110,373	05/05/92
Eichelberger	5,111,278	05/05/92
Chan et al.	5,116,777	05/26/92
Miller	5,130,894	07/14/92
Roy	5,132,244	07/21/92
Hadwin	5,151,775	09/29/92

Henager, Jr., et al.	5,156,909	10/20/92
Zimmerman	5,203,731	04/20/93
Leedy	5,225,771	07/06/93
Bower et al.	5,236,118	08/17/93
Bureau et al.	5,262,351	11/16/93
Bertin et al.	5,270,261	12/14/93
Sanders	5,273,940	12/28/93
Tuckerman	5,274,270	12/28/93
Chebi et al.	5,279,865	01/18/94
Nakanishi et al.	5,284,796	02/08/94
Leedy	5,323,035	06/21/94
Wojnarowski	5,324,687	06/28/94
Leedy	5,354,695	10/11/94
MacDonald	5,363,021	11/08/94
Goossen	5,385,632	01/31/95
Nelson et al.	5,385,909	10/25/94
Shimoji	5,420,458	05/30/95
Miyake	5,424,920	06/13/95
Finnila	5,426,072	06/20/95
Akagi et al.	5,426,363	06/20/95
Yasohama et al.	5,432,444	07/11/95
Carson et al.	5,432,729	07/11/95
Hauck et al.	5,434,500	07/18/95
Leedy	5,451,489	09/19/95
Leedy	5,453,404	09/26/95
Gurtler et al.	5,457,879	10/17/95
Naruse	5,476,813	12/19/95
Gates	5,489,554	02/06/96
Bertin et al.	5,502,667	03/26/96
Leedy	5,512,397	04/30/96
Pati et al.	5,527,645	06/18/96
Koskenmaki et al.	5,529,829	06/25/96
Frye et al.	5,534,465	07/09/96
Toshiaki et al.	5,555,212	09/10/96
Ramm et al.	5,563,084	10/08/96
Leedy	5,571,741	11/05/96
Leedy	5,580,687	12/03/96
Ludwig et al.	5,581,498	12/03/96
Pierrat	5,582,939	12/10/96
Hornbeck	5,583,688	12/10/96
Leedy	5,592,007	01/07/97
Leedy	5,592,018	01/07/97
Heijboer	5,595,933	01/27/97
Noda	5,606,186	02/25/97
Tennant et al.	5,627,112	05/06/97
Leedy	5,629,137	05/13/97
Leedy	5,633,209	05/27/97

Val	5,637,536	06/10/97
Leedy	5,654,127	08/05/97
Leedy	5,654,220	08/05/97
Hudak et al.	5,656,552	08/12/97
Chen et al.	5,675,185	10/07/97
Ohara et al.	5,694,588	12/02/97
Leedy	5,725,995	03/10/98
Weise et al.	5,750,211	05/12/98
Bozso et al.	5,760,478	06/02/98
Okonogi	5,773,152	06/30/98
Rolfson	5,786,116	07/28/98
Zavracky et al.	5,793,115	08/11/98
Ray	5,831,280	11/03/98
Leedy	5,834,334	11/10/98
Leedy	5,840,593	11/24/98
Ito et al.	5,856,695	01/05/99
Sotokawa et al.	5,868,949	02/09/99
Leedy	5,869,354	02/09/99
Sweatt et al.	5,870,176	02/09/99
Davidson	5,880,010	03/09/99
Field et al.	5,882,532	03/16/99
Hübner	5,902,118	05/11/99
Leedy	5,915,167	06/22/99
Leedy	5,946,559	08/31/99
Leedy	5,985,693	11/16/99
Cutter et al.	5,998,069	12/07/99
Leedy	6,008,126	12/28/99
Leedy	6,020,257	02/01/00
Houston	6,045,625	04/04/00
Adamic, Jr.	6,084,284	07/04/00
Gardner et al.	6,097,096	08/01/00
Leedy	6,133,640	10/17/00
Tayanaka	6,194,245 B1	02/27/01
Aleshin et al.	6,197,456 B1	03/06/01
Leedy	6,208,545 B1	03/27/01
Patti	6,236,602 B1	05/22/01
Lin	6,261,728 B1	07/17/01
Leedy	6,288,561 B1	09/11/01
Leedy	6,294,909 B1	09/11/01

#### Foreign Patents

PCT	WO 98/19337	05/1998
UK	GB 2,215,168	09/1989
EPO	EP 0 189 976	08/1986
EPO	EP 0 731 525	09/1996
FRANCE	2641129	12/1988

JAPAN	JP 60-74643	04/1985
JAPAN	JP 02-082564	03/1990
JAPAN	JP 04-083371	03/1992
JAPAN	JP 04-107964	04/1992
JAPAN	JP 402027600A	01/1990

#### Other Documents

"IC Tower Patent: Simple Technology Receives Patent on the IC Tower, a Stacked Memory Technology,"  
<http://www.simpletech.com/whatsnew/memory/@60824.htm> (1998).

Alloert, K., et al., "A Comparison Between Silicon Nitride Films Made by PCVD of  $N_2-SiH_4$  / $A_r$  and  $N_2-SiH_4/He$ ," Journal of the Electrochemical Society, Vol. 132, No. 7, pp. 1763-1766, (July 1985).

Hendricks, et al., "Polyquinoline Coatings and Films: Improved Organic Dielectrics for IC's and MCM's," Eleventh IEEE/CHMT International Electronics Manufacturing Technology Symposium," pp. 361-265 (1991).

Knolle, W.R., et al., "Characterization of Oxygen-Doped, Plasma-Deposited Silicon Nitride," Journal of the Electrochemical Society, Vol. 135, No. 5, pp. 1211-1217, (May 1988).

Nguyen, S.V., "Plasma Assisted Chemical Vapor Deposited Thin Films for Microelectronic Applications, J. Vac. Sci. Technol. Vol. B4, No. 5, pp.1159-1167, (Sep/Oct. 1986).

Olmer, et al., "Intermetal Dielectric Deposition by Plasma Enhanced Chemical Vapor Deposition," Fifth IEEE/CHMT International Electronic Manufacturing Technology Symposium - Design-to-Manufacturing Transfer Cycle," pp. 98-99 (1988).

Runyan, W.R., "Deposition of Inorganic Thin Films," *Semiconductor Integrated Circuit Processing Technology*, p. 142 (1990).

Sze, S.M., "Surface Micromachining," *Semiconductor Sensors*, pp. 58-63 (1994).

Vossen, John L., "Plasma-Enhanced Chemical Vapor Deposition," *Thin Film Processes II*, pp. 536-541 (1991).

Wolf, Stanley, "Basic of Thin Films," *Silicon Processing for the VLSI Era*, pp. 115, 192-193 and 199 (1986).

Copies of the aforementioned documents are listed on the accompanying Form PTO-1449 (submitted in duplicate).

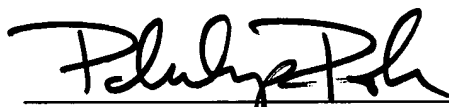
It is respectfully requested that these documents be:

(1) fully considered by the Patent and Trademark Office during the examination of this application; and (2) printed on any patent which may issue on this application.

Applicant requests that a copy of Form PTO-1449, as considered and initialized by the Examiner, be returned with the next communication.

Consideration of the foregoing in relation to this patent application is respectfully requested.

Respectfully submitted,



Philip R. Pol  
Registration No. 51,176  
Agent for Applicant  
FISH & NEAVE  
Customer No. 1473  
1251 Avenue of the Americas  
New York, New York 10020-1104  
Tel.: (212) 596-9000

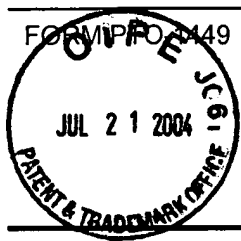
I hereby certify that this  
Correspondence is being  
deposited with the U.S.  
Postal Service as First  
Class Mail in an envelope  
Addressed to:  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450 on

July 19, 2004  
Claire J. Saintilan Goodman



Signature of Person Signing



	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 14	APPLICATION NO. 10/766,557
		APPLICANT Glenn J. Leedy	CONFIRMATION NO. 3092
		FILING DATE January 27, 2004	GROUP 2812

## U.S. PATENT DOCUMENTS

EXAMINE R INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	Re. 34,893	04/04/95	Fujii et al.	257	419	
	2,915,722	12/01/59	Foster	336	115	
	3,202,948	08/24/65	Farrand	336	115	
	3,559,282	02/02/71	Lesk	438	113	
	3,560,364	02/02/71	Burkhardt	324	207.12	
	3,602,982	09/07/71	Emmasingel	29	577	
	3,615,901	10/26/71	Medicus	148	11.5 R	
	3,716,429	02/13/73	Napoli et al.	156	17	
	3,777,227	12/14/73	Krishna et al.	257	578	
	3,868,565	02/25/75	Kuipers	324	207.26	
	3,922,705	11/25/75	Yerman	357	26	
	3,997,381	12/14/76	Wanlass	156	3	
	4,070,230	01/24/78	Stein	156	657	
	4,131,985	01/02/79	Greenwood et al.	29	580	
	4,142,004	02/27/79	Hauser, Jr. et al.	438	792	
	4,251,909	02/24/81	Hoeberechts	29	580	
	4,262,631	04/21/81	Kubacki	118	723MP	
	4,394,401	07/19/83	Shioya et al.	427	574	
	4,401,986	08/30/83	Trenkler et al.	340	870.32	
	4,416,054	11/22/83	Thomas et al.	29	572	
	4,539,068	09/03/85	Takagi et al.	156	614	
	4,585,991	04/29/86	Reid et al.	324	158 P	
	4,612,083	09/16/86	Yasumoto et al.	156	633	
	4,617,160	10/14/86	Belanger et al.	264	40.1	
	4,618,397	10/21/86	Shimizu et al.	156	628	
	4,618,763	10/21/86	Schmitz	250	211R	
	4,663,559	05/05/87	Christensen	313	336	
	4,684,436	08/04/87	Burns et al.	216	65	
	4,693,770	09/15/87	Hatada	156	151	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 14	APPLICATION NO. 10/766,557
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 3092
	FILING DATE January 27, 2004	GROUP 2812

	4,702,336	10/27/87	Maeda et al.	180	197	
	4,702,936	10/27/87	Seibert et al.	427	583	
	4,706,166	11/10/87	Go	361	403	
	4,721,938	01/26/88	Stevenson	338	4	
	4,761,681	08/02/88	Reid	357	68	
	4,784,721	11/15/88	Holmen et al.	156	647	
	4,810,673	03/07/89	Freeman	438	386	
	4,825,277	04/25/89	Mattox et al.	257	639	
	4,857,481	08/15/89	Tam et al.	438	619	
	4,924,589	05/15/90	Leedy	438	6	
	4,940,916	07/10/90	Borel et al.	313	306	
	Re B14,940,916	11/26/96	Borel et al.	315	306	
	4,950,987	08/21/90	Vranish et al.	324	207.23	
	4,952,446	08/18/90	Lee et al.	428	220	
	4,954,865	09/04/90	Rokos	257	378	
	4,957,882	09/18/90	Shinomiya	438	65	
	4,965,415	10/23/90	Young et al.	200	83 N	
	4,966,663	10/30/90	Mauger	205	656	
	4,994,735	02/19/91	Leedy	324	158	
	5,008,619	04/16/91	Keogh et al.	324	207.17	
	5,010,024	04/23/91	Allen et al.	438	659	
	5,020,219	06/04/91	Leedy	29	846	
	5,034,685	07/23/91	Leedy	324	158 F	
	5,070,026	12/03/91	Greenwald et al.	437	3	
	5,071,510	12/10/91	Findler et al.	156	647	
	5,098,865	03/24/92	Machado et al.	438	788	
	5,103,557	04/14/92	Leedy	29	832	
	5,110,373	05/05/92	Mauger	148	33.2	
	5,111,278	05/05/92	Eichelberger	357	75	
	5,116,777	05/26/92	Chan et al.	438	234	
	5,130,894	07/14/92	Miller	361	393	
	5,132,244	07/21/92	Roy	438	477	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. ELM-1 Cont. 14	APPLICATION NO. 10/766,557
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT Glenn J. Leedy	CONFIRMATION NO. 3092
		FILING DATE January 27, 2004	GROUP 2812

	5,151,775	09/29/92	Hadwin	357	80	
	5,156,909	10/20/92	Henager, Jr. et al.	428	334	
	5,203,731	04/20/93	Zimmerman	445	24	
	5,225,771	07/06/93	Leedy	324	158	
	5,236,118	08/17/93	Bower et al.	228	193	
	5,262,351	11/16/93	Bureau et al.	437	183	
	5,270,261	12/14/93	Bertin et al.	437	209	
	5,273,940	12/28/93	Sanders	437	209	
	5,274,270	12/28/93	Tuckerman	257	758	
	5,279,865	01/18/94	Chebi et al.	427	574	
	5,284,796	02/08/94	Nakanishi et al.	437	183	
	5,323,035	06/21/94	Leedy	257	48	
	5,324,687	06/28/94	Wojnarowski	437	225	
	5,354,695	10/11/94	Leedy	438	411	
	5,363,021	11/08/94	MacDonald	315	366	
	5,385,909	01/31/95	Nelson et al.	514	291	
	5,385,632	01/31/95	Goossen	156	630	
	5,420,458	05/30/95	Shimoji	257	622	
	5,424,920	06/13/95	Miyake	361	735	
	5,426,072	06/20/95	Finnila	437	208	
	5,426,363	06/20/95	Akagi et al.	324	239	
	5,432,444	07/11/95	Yasohama et al.	324	240	
	5,432,729	07/11/95	Carson et al.	365	63	
	5,434,500	07/18/95	Hauck et al.	324	67	
	5,451,489	09/19/95	Leedy	430	313	
	5,453,404	09/26/95	Leedy	437	203	
	5,457,879	10/17/95	Gurtler et al.	29	895	
	5,476,813	12/19/95	Naruse	437	132	
	5,489,554	02/06/96	Gates	437	208	
	5,502,667	03/26/96	Bertin et al.	365	51	
	5,512,397	04/30/96	Leedy	430	30	
	5,527,645	06/18/96	Pati et al.	430	5	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 14	APPLICATION NO. 10/766,557
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 3092
	FILING DATE January 27, 2004	GROUP 2812

	5,529,829	06/25/96	Koskenmaki et al.	428	167	
	5,534,465	07/09/96	Frye et al.	437	209	
	5,555,212	09/10/96	Toshiaki et al.	365	200	
	5,563,084	10/08/96	Ramm et al.	437	51	
	5,571,741	11/05/96	Leedy	437	51	
	5,580,687	12/03/96	Leedy	430	5	
	5,581,498	12/03/96	Ludwig et al.	365	63	
	5,582,939	12/10/96	Pierrat	430	5	
	5,583,688	12/10/96	Hornbeck	359	291	
	5,592,007	01/07/97	Leedy	257	347	
	5,592,018	01/07/97	Leedy	257	619	
	5,595,933	01/21/97	Heijboer	439	20	
	5,606,186	02/25/97	Noda	257	226	
	5,627,112	05/06/97	Tennant et al.	438	113	
	5,629,137	05/13/97	Leedy	430	313	
	5,633,209	05/27/97	Leedy	435	228	
	5,637,536	06/10/97	Val	438	686	
	5,654,127	08/05/97	Leedy	430	315	
	5,654,220	08/05/97	Leedy	438	25	
	5,656,552	08/12/97	Hudak et al.	438	15	
	5,675,185	10/07/97	Chen et al.	257	774	
	5,694,588	12/02/97	Ohara et al.	395	566	
	5,725,995	03/10/98	Leedy	430	315	
	5,750,211	05/12/98	Weise et al.	427	579	
	5,760,478	06/02/98	Bozso et al.	257	777	
	5,773,152	06/30/98	Okonogi	428	446	
	5,786,116	07/28/98	Rolfson	430	5	
	5,793,115	08/11/98	Zavracky et al.	257	777	
	5,831,280	11/03/98	Ray	257	48	
	5,834,334	11/10/98	Leedy	438	107	
	5,840,593	11/24/98	Leedy	438	6	
	5,856,695	01/05/99	Ito et al.	257	370	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 14	APPLICATION NO. 10/766,557
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 3092
	FILING DATE January 27, 2004	GROUP 2812

	5,868,949	02/09/99	Sotokawa et al.	216	18	
	5,869,354	02/09/99	Leedy	438	110	
	5,870,176	02/09/99	Sweatt et al.	355	53	
	5,880,010	03/09/99	Davidson	438	455	
	5,882,532	03/16/99	Field et al.	216	2	
	5,902,118	05/11/99	Hübner	438	106	
	5,915,167	06/22/99	Leedy	438	108	
	5,946,559	08/31/99	Leedy	438	157	
	5,985,693	11/16/99	Leedy	438	107	
	5,998,069	12/07/99	Cutter et al.	430	5	
	6,008,126	12/28/99	Leedy	438	667	
	6,020,257	02/01/00	Leedy	438	626	
	6,045,625	04/04/00	Houston	148	33.3	
	6,084,284	07/04/00	Adamic, Jr.	257	506	
	6,097,096	08/01/00	Gardner et al.	257	777	
	6,133,640	10/17/00	Leedy	257	778	
	6,194,245 B1	02/27/01	Tayanaka	438	57	
	6,197,456 B1	03/06/01	Aleshin et al.	430	5	
	6,208,545 B1	03/27/01	Leedy	365	51	
	6,236,602 B1	05/22/01	Patti	365	201	
	6,261,728 B1	07/17/01	Lin	430	30	
	6,288,561 B1	09/11/01	Leedy	324	760	
	6,294,909 B1	09/25/01	Leedy	324	207.17	

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	WO 98/19337	05/1998	PCT	H01L	21/44		
	GB 2,215,168	09/1989	UK	G09G	1/00		
	EP 0 189 976	08/1986	EPO	H01L	31/18		
	EP 0 731 525	09/1996	EPO	H01P	5/00		
	2641129	12/1988	France	H01L	39/04		
	JP 60-74643	04/1985	Japan			ABST	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 14		APPLICATION NO. 10/766,557	
	APPLICANT Glenn J. Leedy		CONFIRMATION NO. 3092	
	FILING DATE January 27, 2004		GROUP 2812	
JP 02-082564	03/1990	Japan		ABST
JP 04-083371	03/1992	Japan		ABST
JP 04-107964	04/1992	Japan		ABST
JP 402027600A	01/1990	Japan		ABST

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL	
	"IC Tower Patent: Simple Technology Receives Patent on the IC Tower, a Stacked Memory Technology," <a href="http://www.simpletech.com/whatsnew/memory/@60824.htm">http://www.simpletech.com/whatsnew/memory/@60824.htm</a> (1998).
	Alloert, K., et al., "A Comparison Between Silicon Nitride Films Made by PCVD of N <sub>2</sub> -SiH <sub>4</sub> /Ar and N <sub>2</sub> -SiH <sub>4</sub> /He," <i>Journal of the Electrochemical Society</i> , Vol. 132, No. 7, pp. 1763-1766, (July 1985).
	Hendricks, et al., "Polyquinoline Coatings and Films: Improved Organic Dielectrics for IC's and MCM's," <i>Eleventh IEEE/CHMT International Electronics Manufacturing Technology Symposium</i> , pp. 361-265 (1991).
	Knolle, W.R., et al., "Characterization of Oxygen-Doped, Plasma-Deposited Silicon Nitride," <i>Journal of the Electrochemical Society</i> , Vol. 135, No. 5, pp. 1211-1217, (May 1988).
	Nguyen, S.V., "Plasma Assisted Chemical Vapor Deposited Thin Films for Microelectronic Applications," <i>J. Vac. Sci. Technol.</i> Vol. B4, No. 5, pp.1159-1167, (Sep/Oct. 1986).
	Olmer, et al., "Intermetal Dielectric Deposition by Plasma Enhanced Chemical Vapor Deposition," <i>Fifth IEEE/CHMT International Electronic Manufacturing Technology Symposium - Design-to-Manufacturing Transfer Cycle</i> , pp. 98-99 (1988).
	Runyan, W.R., "Deposition of Inorganic Thin Films," <i>Semiconductor Integrated Circuit Processing Technology</i> , p. 142 (1990).
	Sze, S.M., "Surface Micromachining," <i>Semiconductor Sensors</i> , pp. 58-63 (1994).
	Vossen, John L., "Plasma-Enhanced Chemical Vapor Deposition," <i>Thin Film Processes II</i> , pp. 536-541 (1991).
	Wolf, Stanley, "Basics of Thin Films," <i>Silicon Processing for the VLSI Era</i> , pp. 115, 192, 193, and 199 (1986).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.